

Amendments to the Specification

Please replace paragraph [0005] with the following amended paragraph:

In photomasks produced for the “phase-shift photolithography” technology, defects may [[be]] cause even more problems because of the required additional processing associated with etching of steps into the quartz substrates. Therefore, in addition to surface pits originating from voids in the original quartz substrate material, surface pit defects can be easily produced during the quartz-etching steps of phase-shift mask fabrication.

Amendments to the Drawings

The attached replacement sheets of drawings include changes to FIGS. 1-3, 5A, 5B, 8A and 8B. These replacement sheets, which include FIGS. 1-3, 5A, 5B, 8A and 8B, replace the drawing sheets on file. In amended FIG. 1, the surface line of the deposited material 104 is enhanced to show the surface of the deposited material 104. In amended FIGS. 5A, 5B, 8A and 8B, scale lines are enhanced to make the graphs clear.

Attachment: Three (3) Replacement Sheets